

**ma-N 1420 – run sheet**

micro resist technology

[nanyte.com/photoresists/ma-n-1420](http://nanyte.com/photoresists/ma-n-1420) · last updated 2026-07-26

**Thickness:** 1.4–3.4  $\mu\text{m}$

**Softbake:** 100 °C · 2 min · hotplate

**Exposure dose:** 550 mJ/cm<sup>2</sup>

**Develop:** Developer ma-D 533/S · Dilution ready-to-use (undiluted) · Time 60 s (50–70 s) · Rinse DI water · Method immersion

**Hardbake:** 100 °C · 30 min